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Multi-phase structured hydrogenated amorphous silicon carbon nitride thin films grown by plasma enhanced chemical vapour deposition

Mohd Azam Abdul Rahman, Wee Siong Chiu, Choon Yian Haw, Ragib Badaruddin, Fatemeh Shariatmadar Tehrani, Mohamad Rusop, Poisim Khiew, Saadah Abdul Rahman

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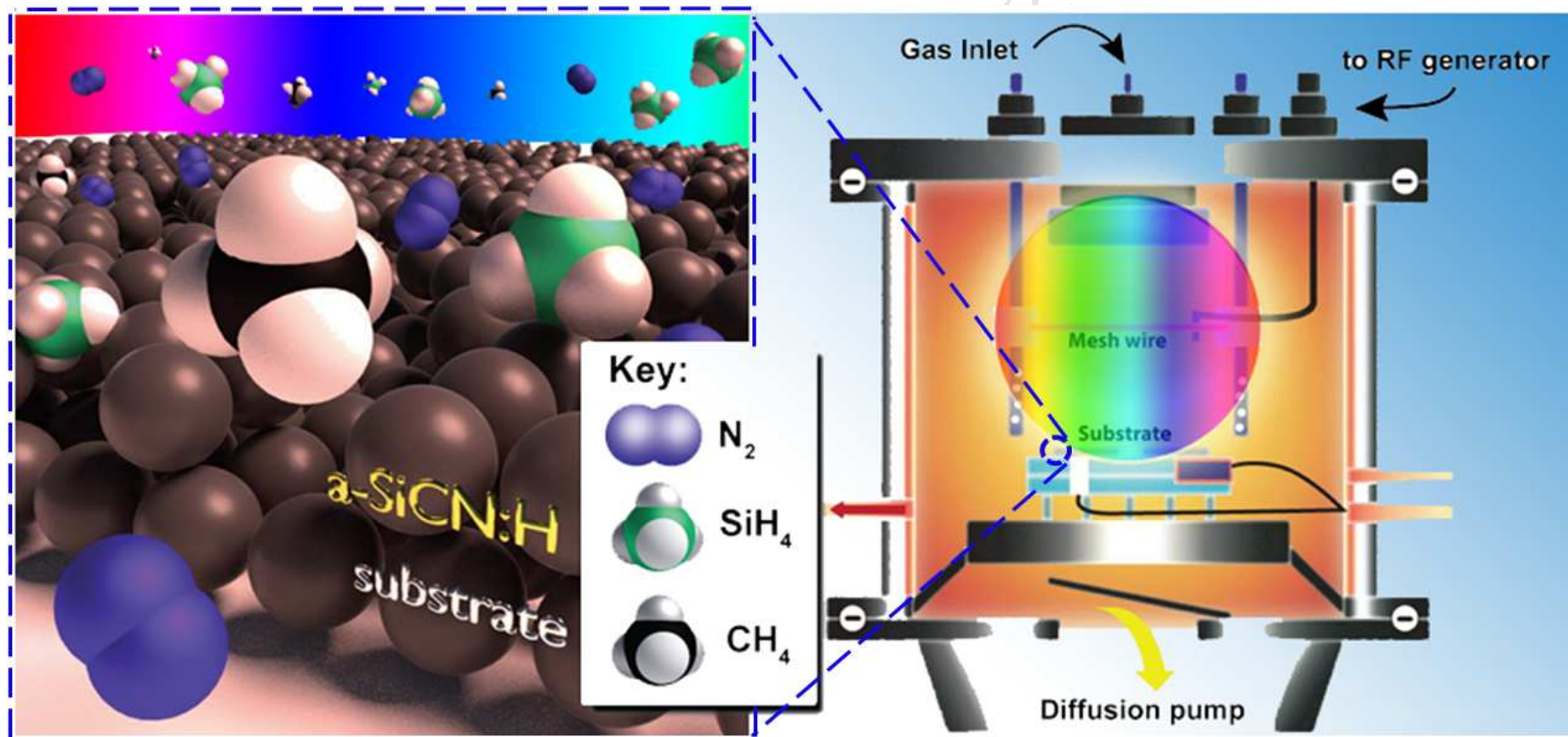
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## Graphical Abstract



Si (100) and glass substrates deposition with  $\text{N}_2$  and  $\text{H}_2$  gas molecules as precursors in PECVD chamber to form SiCN:H thin film

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